

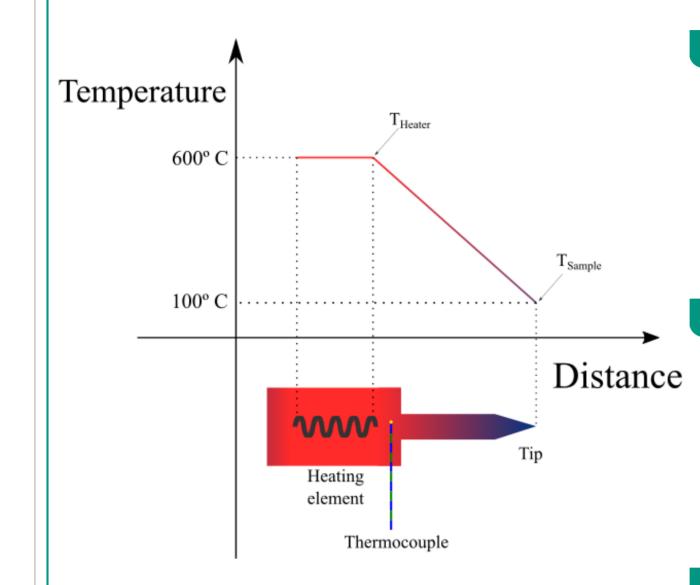


Institute for Applied Materials

## Karlsruhe Institute of Technology

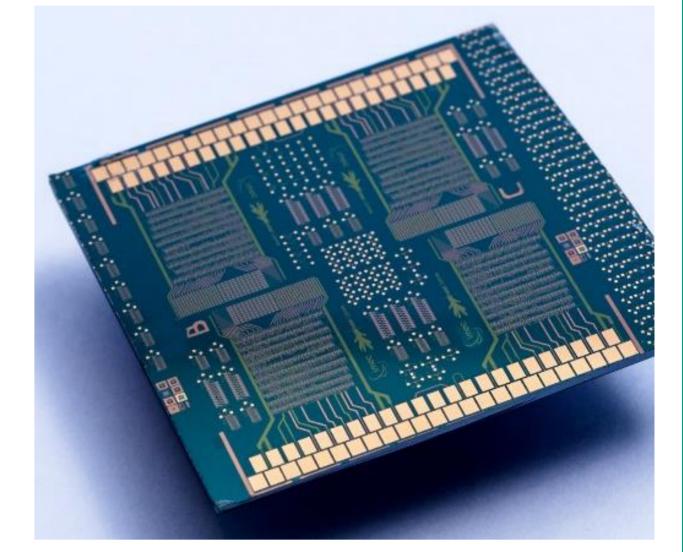
# **Development and application of a high-temperature micromechanics stage** with a novel temperature measurement approach

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### **Motivation and Introduction**

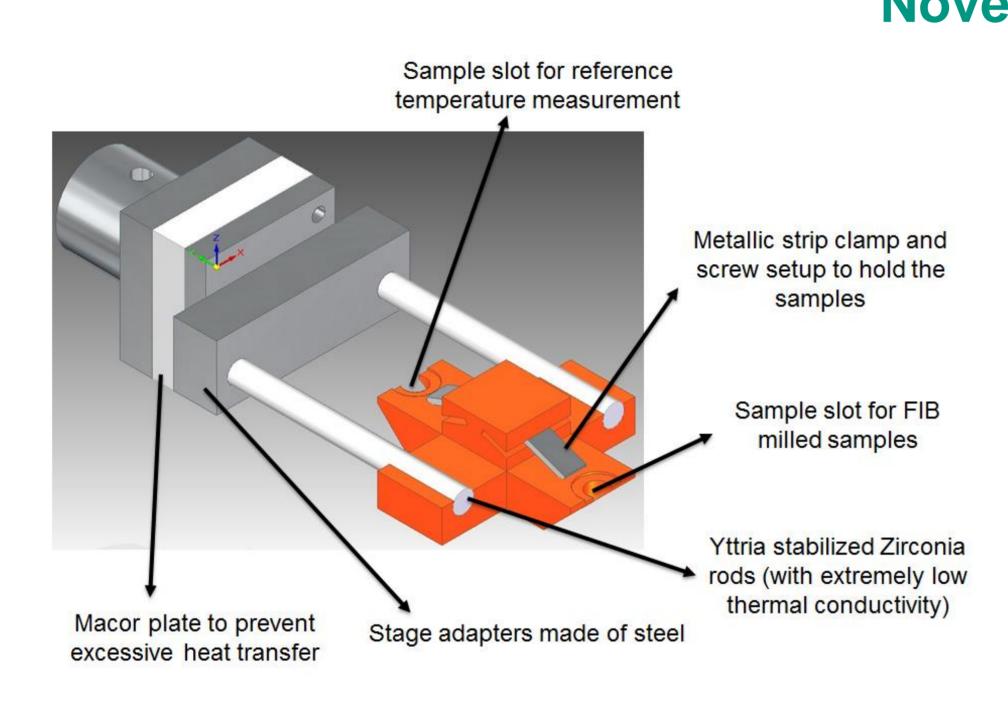
- Despite the advances in the instrumentation of HT micromechanics setups over the last decade, an improvement in the contact temperature measurement is still required to eliminate the inaccuracies in currently available commercial systems.
- Copper alloy thin film systems, well accepted candidates at room

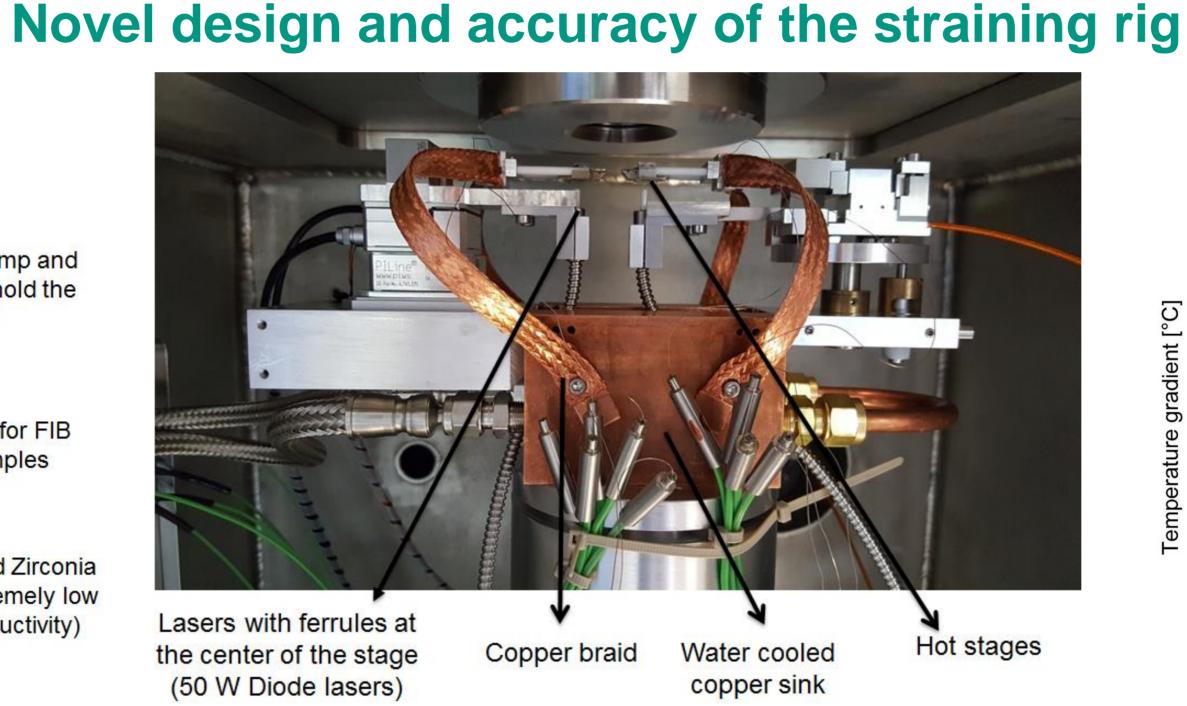


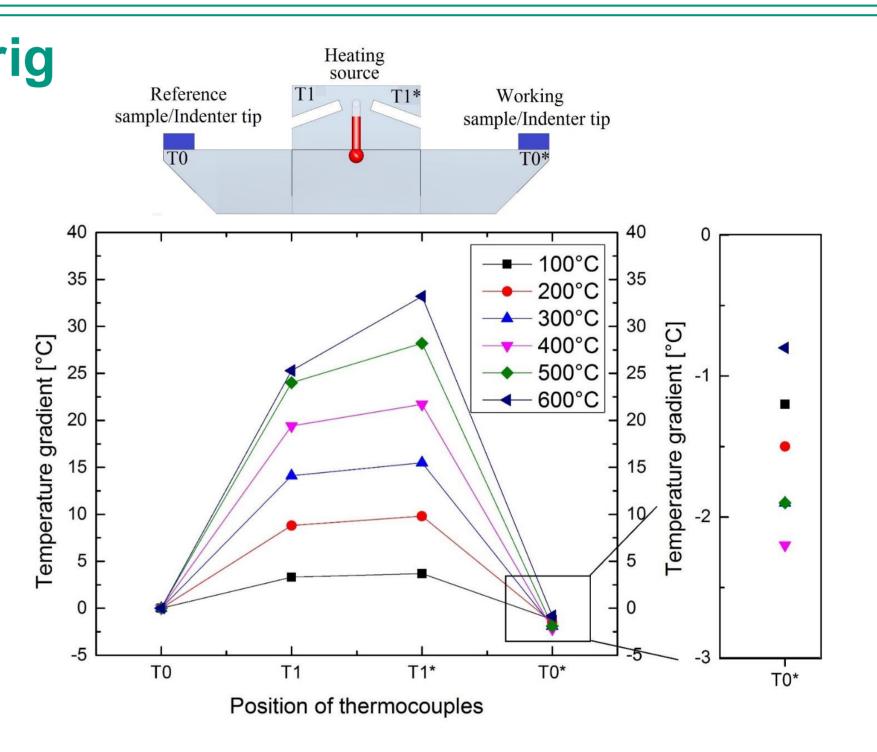
**Current temperature** measurement protocols temperatures for metallization components in electronic circuit systems can behave differently at their service temperatures with respect to their strength retention capabilities.

A novel micromechanical testing design [1] with independent tip and sample heating is developed to characterize Cu-Ag and Cu-Zr systems at high temperatures.

Copper metallization in electronic circuits





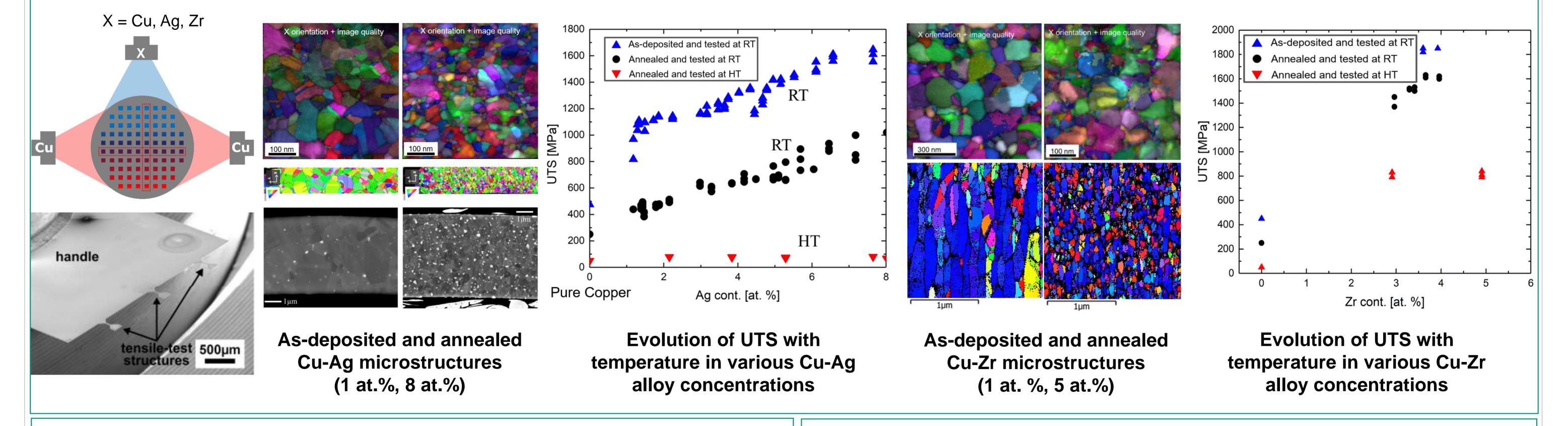


**Design and development of salient features** 

**Proof of concept** 

Hot stage design

### Microstructure and micro tensile characterization of Cu-X thin film systems at various temperatures and conditions



### **Summary: Device development**

Hot stages with symmetric temperature distribution along the two arms and localized central heating sources

#### Summary: Cu-X alloy characterization

- Cu-Ag and Cu-Zr libraries were characterized with microtensile geometries

A series of thermocouples along the both arms providing temperature control of only ±2.5 °C at 600 °C using a reference sample

Faster stabilization times of less than 10 minutes at 600 °C

Cu - Ag system showed a lot of gain in UTS but didn't retain that at higher temperatures

Cu - Zr binary retained the strength even at higher temperatures at the expense of some conductivity

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